

Usage of MWNT dispersed in DMF

Deposition of a photoresist layer (S1813) of 200 nm, using spin coating.

Patterning of photoresist layer (S1813) using suitable mask by photolithography and developed by TMAH solution.

Deposition of **conductive Multiwalled carbon nanotube dispersed in N,N-Dimethylformamide (DMF)**, on the surface using spin coating.

Lift-off the photoresist layer to get the final device.